



Great opportunity to learn about EUVL and EUV Physics in the Upcoming Short Courses

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Greetings. This is Vivek Bakshi from EUV Litho, Inc. In this short blog, I would like to inform you about a great opportunity to learn about EUV lithography and EUV physics on June 3 and 4, 2023. These two short courses will be held, right before the upcoming EUVL Workshop and Supplier showcase from June 5-7.

On June 3rd, we will have a short course on EUV and soft X-ray source physics. In this course we will have two components: The first component will be from Professor Gerry O'Sullivan, who will talk about the physics of EUV, short wavelength sources, and he will focus more on atomic physics. He will explain how short wavelength sources generate EUV photons— that will be of much interest to the folks who are interested in learning more about EUV sources. The second part of the course will be from Professor David Atwood, and he will talk about the physics of EUV photons interacting with matter and EUV optics.

So, this course will be more on the fundamental nature, with total length of about 6-7 hours. And if you're not familiar with the fundamentals, it will be a very good thing to attend this course.

The second course on EUV Lithography will be on June 4th, which is a Sunday. It will have several modules. It will cover pretty much all EUV components. The first component I will cover myself. I will introduce the topic of EUV lithography, how it differs from 193 nanometer lithography, and a high-level description of technology before I discuss EUV sources. The second module is from Professor Jinho Ahn, who will talk about EUV masks, how they are manufactured, how the advanced masks are going to be needed, and various topics related to masks like manufacturing, cleaning, contamination, etc.

Then we have another module by Dr. Patrick Naulleau of CXRO. He will talk about how EUV images are generated and related topics. Plus he will focus on fundamental of EUV resist and the challenges of current and future EUV resists including new resist chemistries for future nodes.

The last module will be by Jan van Schoot of ASML. He will speak on EUVL and high-NA EUVL scanners. As you all know that in order to continue Moore's Law, we are increasing the NA of EUVL scanners. So he will explain the design of high NA scanners and the differences from current EUVL scanners. And he will talk about this anamorphic concept, which is built into high-NA EUVL scanners.

So all in all, a great education opportunity and I hope you will be able to join us. A link to the detailed description of these courses is at the bottom of this blog. These courses are being offered online on Zoom because they are on the weekend. So you'll be able to join us from anywhere, even if you are not at the workshop. If there are any questions, please feel free to write us at info@euvlitho.com. I look forward to seeing you in one of these short courses to take advantage of the great opportunity to learn about EUVL and EUV Physics.



For course descriptions and registration, visit <https://euvlitho.com/education/>.

[Register Today for 2023 EUVL Workshop!](#)

[Click here to view the 2023 EUVL Workshop and Supplier Showcase Final agenda. \(Excel Version\)](#)